

11th International Symposium on SiO₂, Advanced Dielectrics and Related Devices

Boscolo Hotel Plaza, Nice, 13-15 june 2016









CALL FOR PAPERS

You are cordially invited to participate in the 11^{th} edition of the SiO_2 , Advanced Dielectrics and related Devices symposium (SiO₂ 2016) to be held on 13-15 June 2016 in Nice, France.

The biennial SiO₂ symposia series is an international forum on the science and technology of silicabased systems, also including new dielectrics and related applications. It began in 1996 in Agelonde (France). After the 2014 meeting in Cagliari (Italy), the 2016 conference will be hosted by the "Laboratoire de Physique de la Matière Condensée" (LPMC), University of Nice Sophia Antipolis, CNRS.

The objective of the symposium is to provide a forum for the presentation and discussion of recent developments in the physics and chemistry of SiO₂ and of novel dielectric materials in microelectronics, optics, photonics, etc... Oral and poster communications are solicited reporting on original research in these areas. The conference offers the opportunity to highlight future prospects in these fast-moving fields and to enhance exchange and collaboration between scientists. Participation of young researchers (PhD) is especially encouraged.

Please save the date and feel free to announce the symposium to all the people who might be interested in.

For more information, please visit http://sio2-2016.sciencesconf.org

Mourad BENABDESSELAM and Franck MADY

Conference chair and co-chair, LPMC CNRS UMR 7336, University of Nice Sophia Antipolis









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TOPICS

Oral and poster communications are solicited reporting on original research (both experimental and theoretical) in the following areas:

- Electronic and atomic structure
- Optical and electronic properties
- Defect generation and transformation
- Basic mechanisms and modeling
- Radiation effects (including laser processing and harsh environments)
- Dosimetry, sensors, radiation hardening
- Micro-/nano-structuring
- Fiber optics and fiber-based devices
- Microelectronics
- Optoelectronics, photonics

IMPORTANT DATES

- Abstract submission: from January 4, 2016 to March 25, 2016
- Registration: from December 1, 2015 to June 10, 2016 Late registration fees will apply from May 16, 2016





